

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Paul J. Rudeck

Don C. Powell

Serial No.: 10/697,837

Filed: October 28, 2003

For: **USE OF SELECTIVE OXIDATION TO FORM  
ASYMMETRICAL OXIDE FEATURES DURING  
THE MANUFACTURE OF A SEMICONDUCTOR  
DEVICE**



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§ GAU: 2822  
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§ Examiner: Toniae M. Thomas  
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§ Docket No: 2002-0752.00/US  
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§ Confirmation No.: 9305  
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I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail, postage prepaid, in an envelope addressed to: Commissioner for Patents, PO Box 1450, Alexandria, VA 22313-1450, on the date below:

September 16, 2005

Date

Murri Helms

Signature

**COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE**

Applicant submits that each one of the claims of the captioned application is allowable over the cited art for reason of the cited art failing to disclose or suggest the features and/or combination of features as are defined therein. Although applicant acknowledges the Examiner's "Statement of Reasons for Allowance" as set forth with the Notice of Allowance mailed June 16, 2005, applicant submits that the reasons for allowance as provided by the Examiner may represent merely a portion of all of the reasons that support the patentability of the claims of the present application without necessarily being exhaustive.

If there are any matters which may be resolved or clarified through a telephone call, the Examiner is cordially invited to contact the undersigned.

Respectfully submitted,

Kevin D. Martin

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